

Docket No.: A-68359-1/RMA (469113-41)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

First

Named

Inventor:

MALONEY, et al.

Appln.

No.:

10/027,935

Filing

Date:

Title:

December 21, 2001

Apparatus and Method for Chemical-Mechanical Polishing

(CMP) Head Having Direct Pneumatic Wafer Polishing

**Pressure** 

Examiner: ELY, TIMOTHY V

Group Art Unit: 3724

Confirmation No. 2631

Certificate of Mailing

I hereby certify that this correspondence is being deposited in the United States Mail, postage prepaid in an envelope addressed to Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on July 20, 2004.

By: Keslie Arfmann
Leslie Hoffmann

## PETITION FOR EXTENSION OF PERIOD FOR RESPONSE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Pursuant to 37 C.F.R. § 1.136(a), Applicant hereby petitions for an extension of two (2) months (from May 20, 2004 to July 20, 2004) within which to respond to the Office Action dated April 20, 2004. The extension fee of \$420.00 is included in the enclosed check. Please charge any additional fees or credit any overpayment to our Deposit Account No. 50-2319 (Order No. A-68359-1/RMA (469113-41)).

07/26/2004 SZEWDIE1 00000012 10027935

01 FC:1252

420.00 OP

Respectfully submitted,

DORSEY & WHITNEY LLP

By:

R. Michael Ananian, Reg. No. 35,050

Four Embarcadero Center, Suite 3400

San Francisco, CA 94111-4187

Tel: (650) 494-8700 Fax: (650) 494-8771

Date: July 20, 2004